

Title (en)

RETICULAR OBJECTIVE FOR MICROLITHOGRAPHY-PROJECTION EXPOSURE INSTALLATIONS

Title (de)

REMA-OBJEKTIV FÜR MIKROLITHOGRAPHIE-PROJEKTIONSBELICHTUNGSANLAGEN

Title (fr)

OBJECTIF A RETICULE POUR UNITES D'EXPOSITION PAR PROJECTION POUR MICROLITHOGRAPHIE

Publication

**EP 0888570 A1 19990107 (DE)**

Application

**EP 97952867 A 19971203**

Priority

- DE 19653983 A 19961221
- EP 9706760 W 19971203

Abstract (en)

[origin: DE19653983A1] A reticular objective is realized by introduction of a few (3-5 units) aspherical lenses (7, 11, 17) of high-quality correction with a low number of lenses (few that 10), and low path in glass (maximum 25-30 % of the object-reticle distance), thus enhancing efficiency.

IPC 1-7

**G02B 13/18**; **G02B 13/22**; **G03F 7/20**

IPC 8 full level

**H01L 21/027** (2006.01); **G02B 13/14** (2006.01); **G02B 13/18** (2006.01); **G02B 13/22** (2006.01); **G02B 13/24** (2006.01); **G03F 7/20** (2006.01)

CPC (source: EP KR US)

**G02B 13/143** (2013.01 - EP US); **G02B 13/18** (2013.01 - KR); **G03F 7/70066** (2013.01 - EP US); **G03F 7/70225** (2013.01 - EP US)

Citation (search report)

See references of WO 9828644A1

Designated contracting state (EPC)

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